AMENDMENTS TO THE SPECIFICATION

Page 4, Para 2

According to the purposes of the present invention, the second embodiment discloses a modulation used in an optical interference display. This modulation comprises at least a light-incidence electrode and a light-reflection electrode, and the light-incidence electrode comprises the substrate, an absorption layer and a dielectric layer. The substrate is the first conductive transparent layer. The first dielectric layer is formed on the first conductive transparent layer, e.g. substrate, and the second conductive transparent layer is then formed on the first dielectric layer by sputtering. Subsequently the second dielectric layer is deposited on the second conductive layer. The absorption layer comprises the first dielectric layer and the second conductive transparent layer. The light is actually absorbed by the first (substrate) and the second conductive transparent layer, wherein the direction of the ~~axes~~ axis and the orientation of lattice of the first conductive transparent and ~~the axes and lattice of~~ the direction of the axis and the orientation of lattice of the second conductive transparent layer could be different.

Page 4 bridging Page 5, Para 3

According to the objectives of the present invention, the third embodiment provides a modulation used in an optical interference display. This modulation comprises at least a light-incidence electrode and a light-reflection electrode, and the light-incidence electrode comprises a substrate, an absorption layer and a dielectric layer. The substrate is the first conductive transparent layer. On top of the substrate, at least two dielectric layers and two conductive transparent layers are formed in turns. The absorption layer comprised all layers apart from the dielectric layer on the top and the substrate. The light is actually absorbed by the substrate and the conductive transparent layers, wherein the ~~axes~~ axis and the orientation of the lattice ~~of axes~~ of every neighboring conductive transparent layer could be different.

Page 7 bridging Page 8, Para 3

The transparency of the conductive transparent material is normally high, that is, more than 80%; while the ideal transparency of light incidence electrode 302 is between about

between 20% and 70%. The method of decreasing the transparency of substrate 3021 comprises increasing the thickness of the substrate 3021, adjusting the manufacturing parameters to decrease the purity of the substrates and so on. The thicker the substrate is, the lower the transparency that can be achieved. Therefore, increasing the thickness of the substrate decreases the transparency. Moreover, ~~adjusting~~ the parameters of manufacturing ~~parameters to produce a~~ the substrate are adjusted to produce a substrate with various orientations of the ~~with disordered~~ lattice ~~makes various axes~~ in ~~every~~ different ~~part~~ parts of the substrate, that is, the substrate is made of amorphous or polycrystalline material. The method disclosed above is another method to decrease the transparency of the substrate. Furthermore, in order to decrease the transparency of substrate, a low purity substrate can be made by increasing the impurities in the substrate (more than 100 ppm). It disorders the lattice of the substrate. Also, the impurities in the substrates normally have low transparency. It helps to decrease the overall transparency as well. The three methods discussed herein can be either used alone, or in combination.

Page 8, Para 2

The substrate 5021 and the conductive transparent layer 5023 function as an absorption layer. However, the substrate is formed on a glass plate (not shown in the figure) and the conductive transparent layer is formed on the top of the dielectric layer 5022. ~~The~~ Therefore, the ~~lattice is~~ lattices of the substrate and conductive transparent layer are different ~~disordered~~ and the axes of the substrate and conductive transparent layer ~~each~~ are toward different directions. Therefore, the transparent rate of the absorption layer can be similar to the transparent rate of a well-known absorption layer.

Page 9 bridging Page 10, Para 3

Substrate 6021, the first conductive transparent layer 6023 and the second conductive transparent layer 6025 function as an absorption layer. The first dielectric layer 6022 formed on the substrate 6021 influences the formation of the first conductive transparent layer 6023. ~~The lattice is therefore disordered.~~ ~~Also~~ However, the orientations of the lattice of the second dielectric layer 6024 and the first dielectric layer 6022 are different because of the different condition during deposition. ~~And~~ Therefore, the direction of the axis of the lattice of the second conductive transparent layer 6025 is different from the ~~ones in~~ direction of the axis of the lattice

of the first conductive transparent ~~dielectric~~ layer 6023 and substrate 6021. The formation of the orientation of the lattice and ~~axes~~ the direction of the axis of every part of the conductive transparent layer are all different. Further, the formation of multilayer can also increase the ~~thinness~~ thickness of an absorption layer. Therefore the transparency of the absorption layer can be the same as the transparency of a well-known absorption layer.